

# Eunah Ko

## List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/5356237/publications.pdf>

Version: 2024-02-01

11

papers

375

citations

1307594

7

h-index

1372567

10

g-index

11

all docs

11

docs citations

11

times ranked

412

citing authors

#	ARTICLE	IF	CITATIONS
1	Optimization of double metal-gate InAs/Si heterojunction nanowire TFET. <i>Semiconductor Science and Technology</i> , 2020, 35, 075024.	2.0	8
2	Steep Slope Silicon-on-Insulator Field Effect Transistor with Negative Capacitance: Analysis on Hysteresis. <i>Journal of Nanoscience and Nanotechnology</i> , 2019, 19, 6128-6130.	0.9	1
3	Steep Slope Silicon-On-Insulator Feedback Field-Effect Transistor: Design and Performance Analysis. <i>IEEE Transactions on Electron Devices</i> , 2019, 66, 286-291.	3.0	33
4	Analysis on the Operation of Negative Differential Resistance FinFET With Pb(Zr <sub>0.52</sub> Ti <sub>0.48</sub> )O <sub>3</sub> Threshold Selector. <i>IEEE Transactions on Electron Devices</i> , 2018, 65, 19-22.	3.0	13
5	Super steep-switching (SS $\approx 2$ mV/decade) phase-FinFET with Pb(Zr <sub>0.52</sub> Ti <sub>0.48</sub> )O <sub>3</sub> threshold switching device. <i>Applied Physics Letters</i> , 2018, 113, .	3.3	8
6	Steep switching devices for low power applications: negative differential capacitance/resistance field effect transistors. <i>Nano Convergence</i> , 2018, 5, 2.	12.1	60
7	Negative Capacitance FinFET With Sub-20-mV/decade Subthreshold Slope and Minimal Hysteresis of 0.48 V. <i>IEEE Electron Device Letters</i> , 2017, 38, 418-421.	3.9	100
8	Effective drive current in steep slope FinFET (vs. conventional FinFET). <i>Applied Physics Letters</i> , 2017, 111, .	3.3	5
9	Sub-60-mV/decade Negative Capacitance FinFET With Sub-10-nm Hafnium-Based Ferroelectric Capacitor. <i>IEEE Journal of the Electron Devices Society</i> , 2017, 5, 306-309.	2.1	57
10	Layout engineering to suppress hysteresis of negative capacitance FinFET. , 2017, , .		0
11	Vertical Tunnel FET: Design Optimization With Triple Metal-Gate Layers. <i>IEEE Transactions on Electron Devices</i> , 2016, 63, 5030-5035.	3.0	90